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**PATENT APPLICATION
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

SUZUKI, Takako, et al.

Attorney Docket No.: Q67844

#3
D.G.
4-24-02

Divisional of Appln. No. 09/322,978

Group Art Unit: 1752

Confirmation No.: Unknown

Examiner: Unknown

Filed: February 28, 2002

For: POSITIVE PHOTORESIST COMPOSITION AND PROCESS FOR
FORMING RESIST PATTERN USING SAME

**PROPRIETARY INFORMATION DISCLOSURE STATEMENT
UNDER 37 C.F.R. §§ 1.97 and 1.98
AND IN ACCORDANCE WITH MPEP § 724**

Commissioner for Patents
Washington, D.C. 20231

Sir:

In accordance with the duty of disclosure under 37 C.F.R. § 1.56, Applicant hereby notifies the U.S. Patent and Trademark Office of the following U.S. Patent applications which the Examiner may deem material to an examination of the above-identified application.

<u>Serial No.</u>	<u>Applicant's Name</u>	<u>Filing Date</u>
09/322,023	Takako Suzuki et al.	June 1, 1999

Applicant is not providing a copy of the listed copending application. See 37 C.F.R. §1.98(d). However, if desired, a duplicate will be provided upon request.

PROPRIETARY INFORMATION DISCLOSURE STATEMENT
U.S. Appln. No. 09/322,978

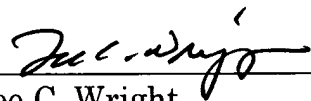
The present Information Disclosure Statement is being filed: (1) No later than three months from the application's filing date for an application other than a continued prosecution application (CPA) under §1.53(d); (2) Before the mailing date of the first Office Action on the merits (whichever is later); or (3) The first Office Action after filing a request for continued examination (RCE) under §1.114, and therefore, no Statement under 37 C.F.R. § 1.97(e) or fee under 37 C.F.R. § 1.17(p) is required.

The submission of the listed documents is not intended as an admission that any such documents constitute prior art against the claims of the present application. Applicant does not waive any right to take any action that would be appropriate to antedate or otherwise remove any listed document as a competent reference against the claims of the present application.

This paper contains proprietary information and is being submitted in accordance with the procedures of MPEP § 724.

Respectfully submitted,

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Date: February 28, 2002

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